

DECLARATION
Serial No. 10/360,236
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**IN THE UNITED STATES
PATENT AND TRADEMARK OFFICE**

PATENT APPLICATION

Applicant: Fodor, et al.

Case: 8295/DSM/BCVD/JW

Serial No.: 10/684,054

Filed: October 10, 2003

Examiner: Fuqua, Shawntina T.

Group Art Unit: 3742

Confirmation No.: 5247

Title: **SUBSTRATE HEATER ASSEMBLY**

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

**DECLARATION OF MARK A. FODOR, SOPHIA M. VELASTEGUI,
SOOVO SEN, VISWESWAREN SIVARAMAKRISHNAN,
PETER WAI-MAN LEE, AND MARIO DAVID SILVETTI
UNDER 37 C.F.R. §1.131**

We, Mark A. Fodor, Sophia M. Velastegui, Soovo Sen, Visweswaren Sivaramakrishnan, Peter Wai-Man Lee, and Mario David Silvetti declare as follows:

1. We are the inventors of above-captioned patent application.
2. The invention which forms the subject matter of the above-captioned patent application was conceived of and reduced to practice on or before July 8, 2003, as evidenced by Exhibit A, enclosed herewith.
3. Exhibit A is a copy of an invention alert that was submitted to the Applied Materials Patent Department on or before July 8, 2003 as part of an invention disclosure that forms the basis of the present application.

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4. Exhibit A describes a substrate heater assembly for supporting a substrate of a predetermined standardized diameter during processing. The substrate heater includes a body having an upper surface and a lower surface, and a heating element embedded within the body. A substrate support surface is formed in the upper surface of the body and defines a portion of a substrate receiving pocket. An annular wall is oriented perpendicular to the upper surface and has a length of at least one half a thickness of the substrate. The wall bounds an outer perimeter of the substrate receiving pocket and has a diameter less than about 0.5 mm greater than the predetermined substrate diameter. A continuous lip may protrude from the upper surface and circumscribe the wall. The continuous lip has an inner portion joined with a bevel flaring outward from the wall. The substrate heater may be disposed in a chemical vapor deposition chamber. See pages 5-8, paragraphs 7-8, and corresponding Figures.

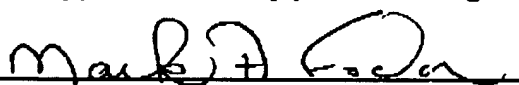
5. Exhibit A is offered as supporting evidence that the apparatus of the present invention – as recited, for example, in independent claims 1, 21 and 22 – was conceived of and reduced to practice on or before the July 8, 2003 first-publication date of United States Patent No. 6,589,352.

We further declare that all statements made herein of our own knowledge are true and that all statements made on information and belief are believed to be true; and further, that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code and that such willful false statements may jeopardize the validity of the application or any patent issuing thereon.

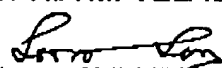
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Date

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Date


MARK A. FODOR


SOPHIA M. VELASTEGUI


SOOVO SEN

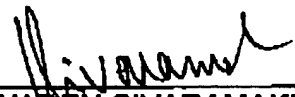
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